

**Amendments to the Abstract:**

Please replace the Abstract paragraph on page 38 with the following:

A method of processing a substrate having an optical surface includes using an interferometer which includes optics for providing a beam of measuring light. The optics polarize the beam of measuring light such that a tangential polarization component continuously increases relative to a radial polarization component with increasing distance from an optical axis. The substrate is positioned in the beam of measuring light. Using the system, the interferometer determines a surface map of the optical surface, and determines deviations of the optical surface from a target shape.